REPORT DOCUMENTATION PAGE

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14. ABSTRACT							
This project was focused on the	ne developr	nent of switches us	ing phase ch	ange mater	rials from chalcogenide compounds.		
					del capable of describing the device		
nonlinear behaviors was introd		-			and appears or accompany and action		
15. SUBJECT TERMS							
phase change materials (PCM	I), microele	ctromechanical svs	tems (MEMS)			
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a. REPORT b. ABSTRACT c	ABSTRACT	OF PAGES	Mina Rais-Zadeh				
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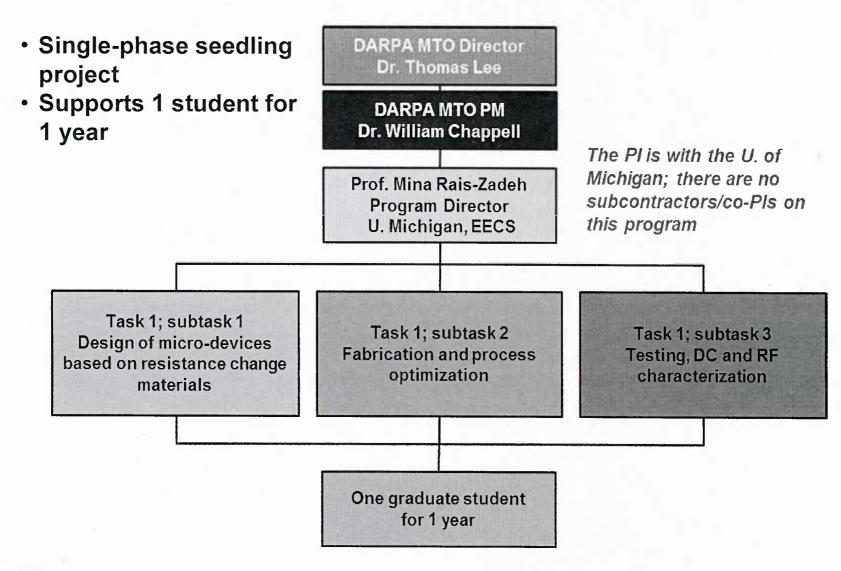
Micro-Devices Using Resistance Change Materials (MODERN Materials)

PI: Mina Rais-Zadeh University of Michigan, Ann Arbor, MI

DARPA Final Review Meeting 03/07/2014



Organization Chart





Outline

- Motivation & Introduction
- GeTe Vias as RF Ohmic Switches
 - Intrinsic RF Properties
 - Phase-Transition Characteristics
 - Power Handling Capability
- New GeTe Switch Design
 - Design Consideration
 - RF & Heat Simulation
 - Initial Measurement Result
- Future Plans



Outline

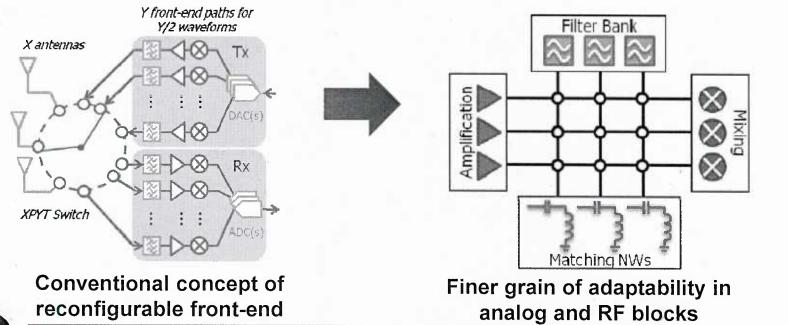
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From DARPA-BAA-12-13, RF FPGA

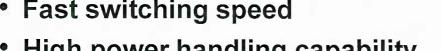
RF-FPGA Program Goal

- To enable a common hardware architecture that facilitates reutilization of the same set of RF front-end components across different applications making the transceiver chain programmable.
- "...this goal can only be achieved by investigating the ability to adapt, switch or otherwise alter the RF front end."
- This project is focused on the implementation of a new RF switch using resistance change or phase change materials.



RF Switches - Requirements

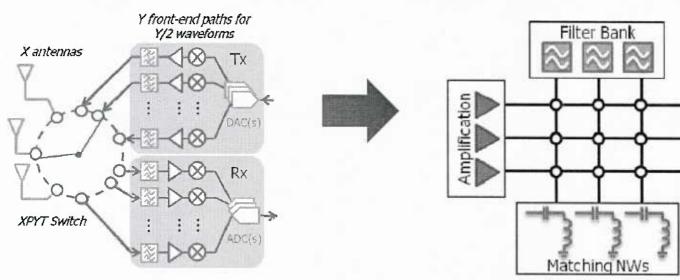
- Low insertion loss & good isolation
- Small size (high-density integration)
- High yield and reliability
- Fast switching speed
- High power handling capability





These all can be potentially achieved using phase change switches

 Post CMOS/Si compatibility? (note there are high power GaN RF switches with ns switching time and >10W power handling capability)

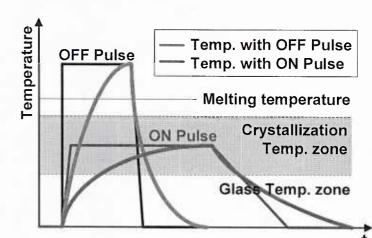


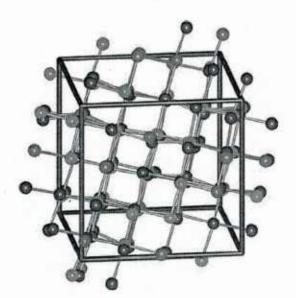
Conventional concept of reconfigurable front-end

Finer grain of adaptability in analog and RF blocks

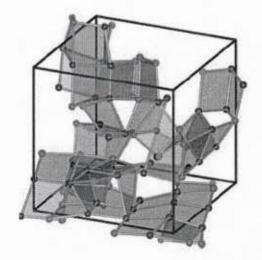
Phase Change Materials

- Two phases: amorphous and crystalline states
- Phase transition occurs when a specific heat condition is applied

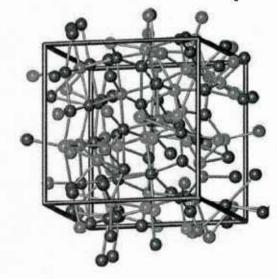




Crystalline state (low resistance)



Ge₂Sb₂Te₅ melt

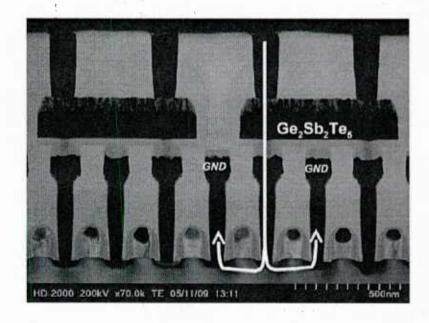


Amorphous state (high resistance)

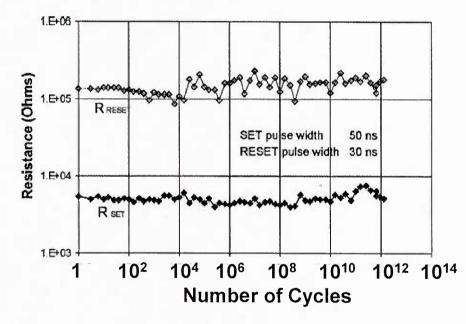


Phase Change Materials

- Benefits: high-density integration, fast switching speed (ns range), long life cycles (> 10⁸ or 10⁹)
- Exploited as non-volatile random-access memory or optical DVD



256 Mb PRAM using 100nm technology; a cell size is 0.166 μm²



Cycling performance of the set and reset states of a single PC memory cell

S. Raoux, et al, EPCOS 2009, Sep. 2009.

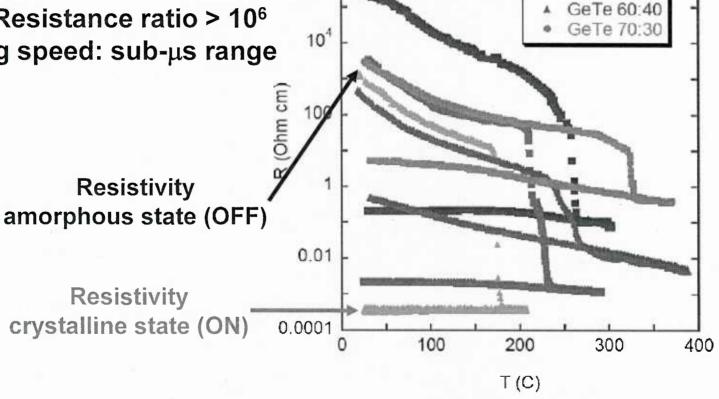
Material Choice for RF Switching: GeTe

10⁶

ON resistivity as low as 2×10^{-4} Ω ·cm

OFF/ON Resistance ratio > 10⁶

Switching speed: sub-µs range



Resistivity vs. temperature in various stoichiometric composition of GeTe



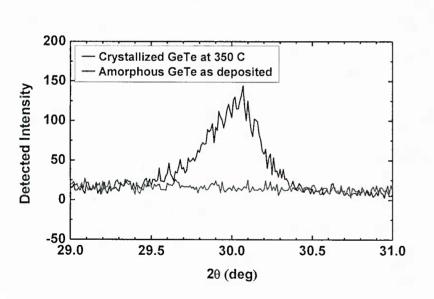
GeTe 30:70

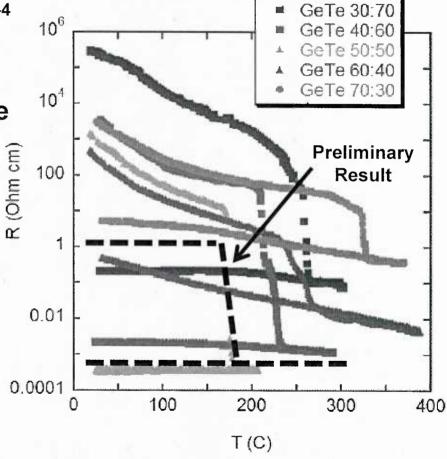
GeTe 40:60

GeTe 50:50

Material Choice for RF Switching: GeTe

- ON resistivity as low as 2 \times 10⁻⁴ Ω ·cm
- OFF/ON Resistance ratio > 10⁶
- Switching speed: sub-μs range





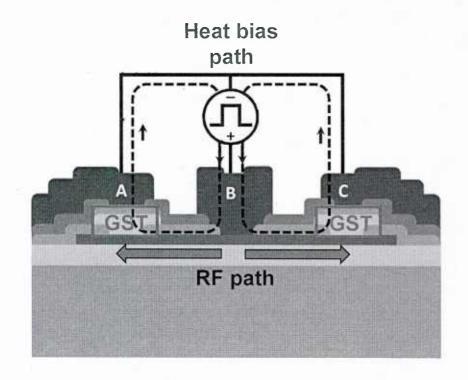
XRD plot of a GeTe thin film deposited on a silicon substrate from 29° to 31° of 20

Resistivity vs. temperature in various stoichiometric composition of GeTe

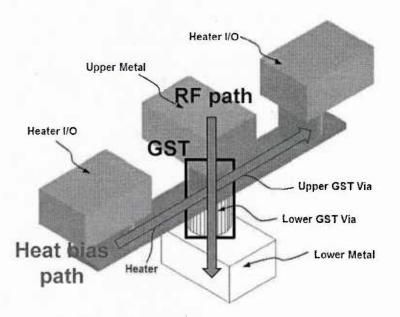


Direct Heating vs. Indirect Heating

- Direct heating: same path for RF and heating bias
- Indirect heating: separated paths for RF and heating bias



Direct heating



Indirect heating

C.-Y. Wen, et al, IEDM 2010, Dec. 20' K. N. Chen, et al, IEEE EDL, Jan. 200

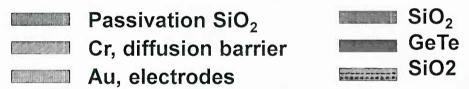
Outline

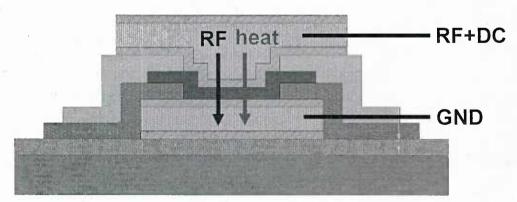
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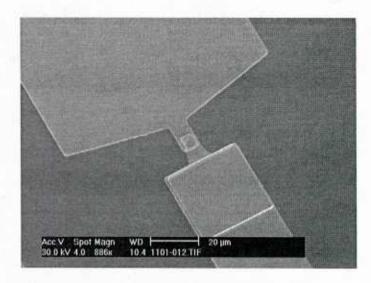
GeTe Vias as RF Ohmic Switches

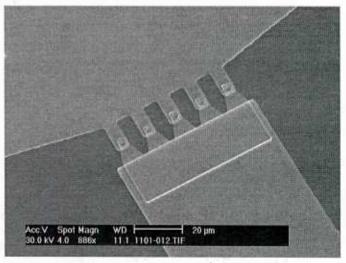
- Fundamental properties of GeTe were characterized using two different switch configurations.
- Direct heating is used for phase transition.





Cross-section of PC switch



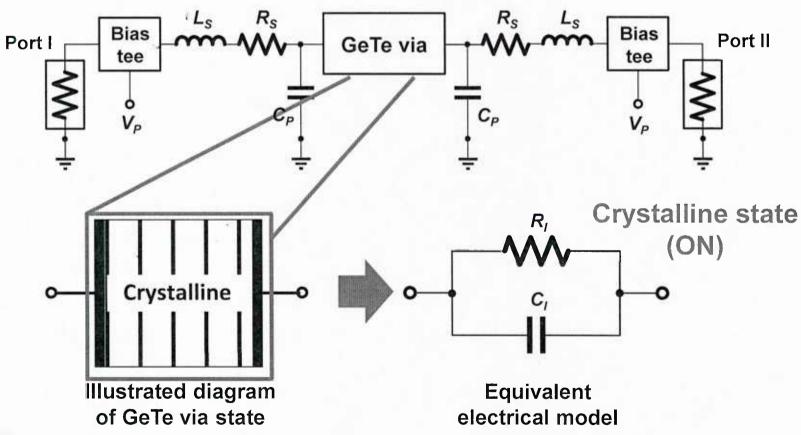


SEM view of fabricated PC switches



Intrinsic RF Properties Equivalent Electrical Model

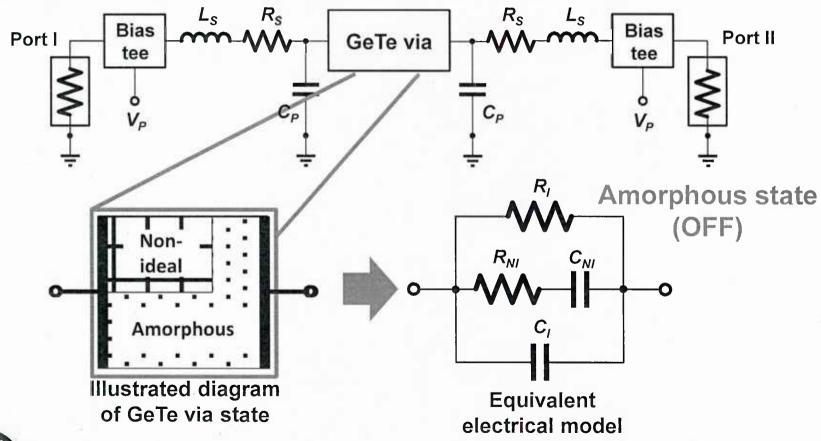
- A new electrical model is proposed for phase-change switches.
- GeTe via is conventionally modeled with a parallel connection of an intrinsic resistor and a capacitor.





Intrinsic RF Properties Equivalent Electrical Model

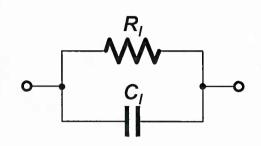
- With incomplete transition, non-ideal state grains could exist.
- Grains that undergo incomplete phase transition are modeled by adding another parallel branch to the electrical model
- Size reduction is important for good isolation at high frequency.

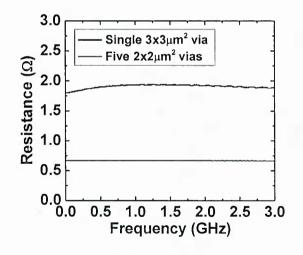




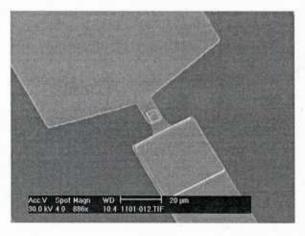
Intrinsic RF Properties Lumped Element Values (Crystalline State)

- In the crystalline state (ON), R_I models the low resistance of the via.
- C₁ is the intrinsic parallel plate capacitance (which cannot be ignored as the permittivity of the phase change layer is high.)

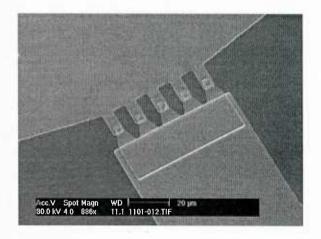




Extracted R_I
Crystalline state (ON)



SEM view of single $3 \times 3 \mu m^2$ via

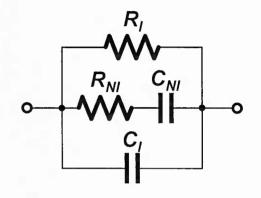


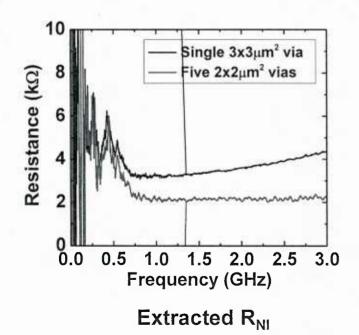
SEM view of five $2 \times 2 \mu m^2$ via

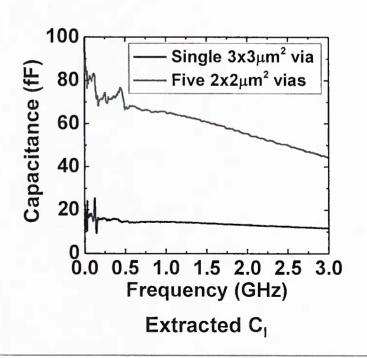


Intrinsic RF Properties Lumped Element Values (Amorphous State)

- In amorphous state (OFF), R_I models the OFF state leakage resistance, reaching 10⁵ times the ON resistance.
- At high frequencies, $R_{\rm NI}$ and $C_{\rm NI}$ provide additional feed-through path and reduce the isolation level (unwanted).



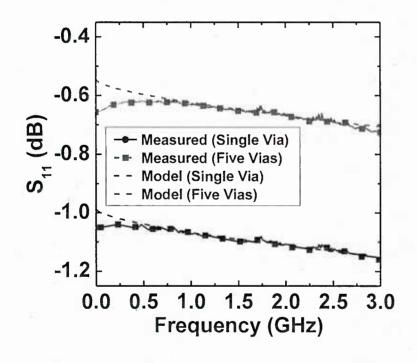


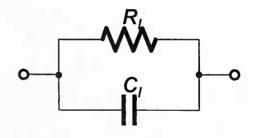




Intrinsic RF Properties Measured S₁₁ (Crystalline State)

- Measured S₁₁ from one-port GeTe switches in single-via and fivevia configurations.
- Parasitic capacitance of 5via device < 5x capacitance of 1via device





	Single via	Five vias			
R _I	2.62 Ω	1.35 Ω			
C _I	15 fF	60 fF			
Cutoff Freq	4.0 THz	1.96 THz			

Measured S₁₁ at crystalline state

Lumped element values

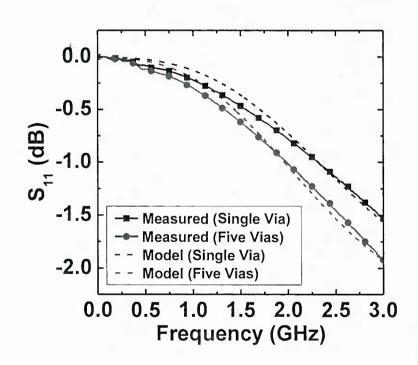


Intrinsic RF Properties Measured S₁₁ (Amorphous State)

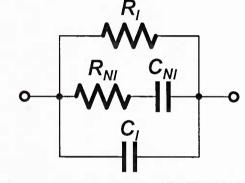
 Measured S₁₁ from one-port GeTe switches in single-via and fivevia configurations.

As expected, the incomplete phase transition affect the OFF-state

isolation at higher frequencies.



Measured S₁₁ at amorphous state



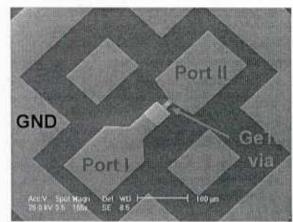
	Single via	Five vias	
R_{l}	200 kΩ	100 kΩ	
C,	15 fF	60 fF	
R _{NI}	6 kΩ	1 kΩ	
C _{NI}	1 fF	1 fF	

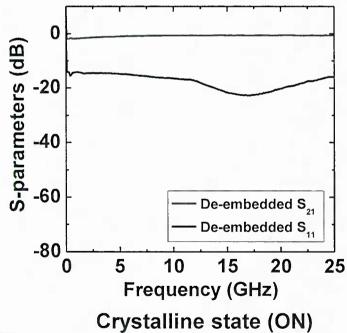
Lumped element values

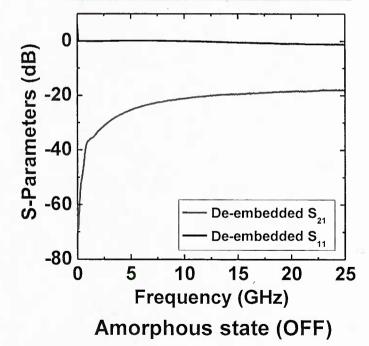


Intrinsic RF Properties Measured S-Parameters (Two-Port)

- Insertion loss (S₂₁ at ON state)
 - 0.5 dB @ 10 GHz, 1.0 dB @ 20 GHz
- Isolation (S₂₁ at OFF state)
 - 20 dB @ 10 GHz, 18 dB @ 20 GHz



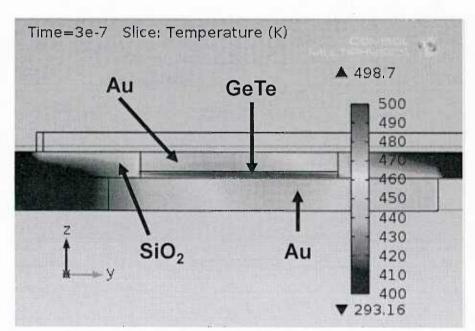




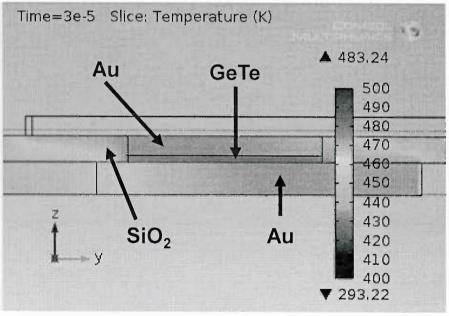


Intrinsic RF Properties Phase-Transition Simulation

- Amorphization time < 1 μs
- Crystallization time < 50 μs



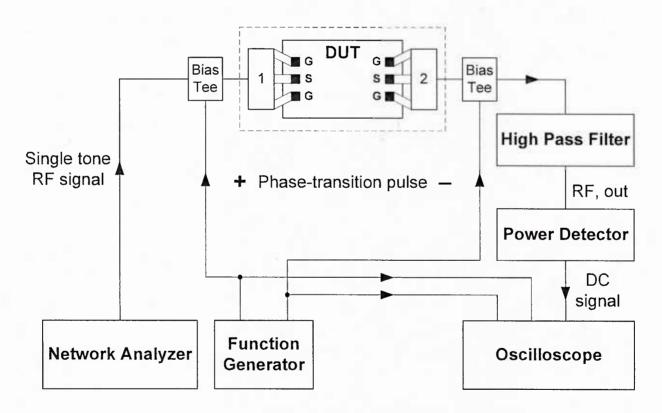
Simulated temperature distribution when 3.5 V is applied for 300 ns for amorphization



Simulated temperature distribution when 2.0 V is applied for 30 μs for crystallization

Intrinsic RF Properties Measured Switching Speed

 Phase transitions can be realized by applying voltage or current pulses to heat the GeTe material.

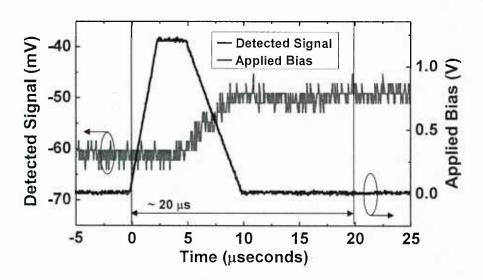


Measurement system diagram

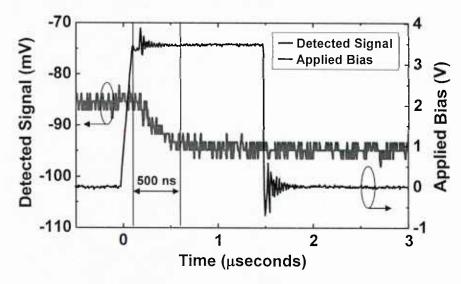


Intrinsic RF Properties Measured Switching Speed

- Crystallization takes ~ 20 μs.
- Amorphization takes < 1 μs.
- For more reliable switching, bias voltage amplitude and duration should be further adjusted and optimized.
- Also, smaller size vias will be placed in parallel to ensure complete phase transition, while maintaining a small ON resistance.



Switching characteristics for crystallization



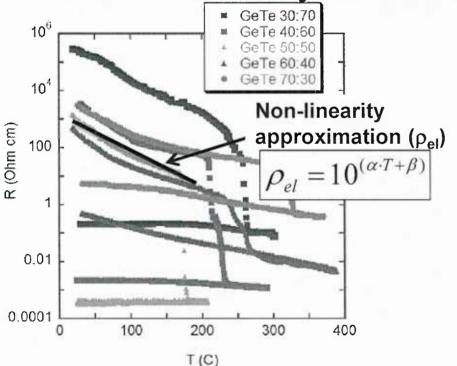
Switching characteristics for amorphization



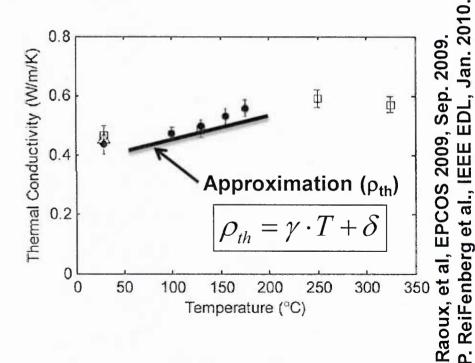
Intrinsic RF Properties Analysis on Power Handling Capability

- Non-linear behavior of GeTe switches is dominantly observed at the amorphous state.
- Both electrical and thermal resistivites show temperature variation.

This is accelerated by the Poole-Frenkel Effect.



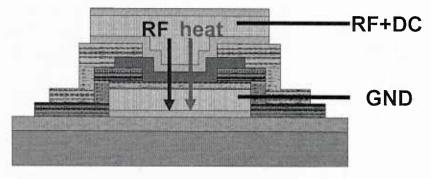




Thermal resistivity change

Analysis on Power Handling Capability Overview

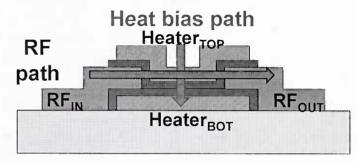
- A new power handling analysis model for GeTe switch is proposed and verified by comparing simulation and measurement results. This model can be utilized to estimate IIP₃ or P_{1dB} of various types of phase change switch structures and materials.
- The power handling performance of directly heated two-port GeTe is measured and compared with simulation results, showing good agreement.



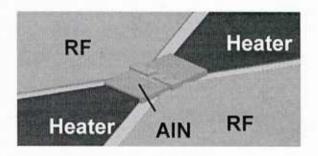
Type A: directly heated twoport GeTe switch

Analysis on Power Handling Capability Overview

- To improve the performance, Type B: a four-terminal switch with separate RF and heater electrodes is proposed and fabricated. Preliminary results show very promising performance.
- Other designs (Type C) are also under consideration that offer simpler fabrication process and better power handling capability (at the cost of higher power consumption).



Type B: four-terminal directly heated switch with separate RF and heater electrodes



Type C: four-terminal indirectly heated switch with separate RF and heater electrodes



Jelmini and Y. Zhang, Journal of Applied hysics, 102, 054517 (2007). Ohn Simmons, Physical Review, 1967.

Power Handling Analysis Poole-Frenkel Effect

- The change in electrical resistivity in the amorphous state is dominated by the Poole-Frenkel Effect (electrical conduction in dielectrics due to thermal fluctuation under an electric field).
- Although this effect is not as dominant at the ON state due to a smaller voltage drop across the PC layer, resistivity change of GeTe can also be described when crystallized using the same model with different trapping energy level (E_c) and effective level of related carriers (N_T).

$$\rho_{PC} = \frac{kT \cdot \tau_0}{(q\Delta z)^2 \cdot N_T} \cdot e^{(E_C - E_F)/kT} \cdot \cosh^{-1} \left(\frac{qV}{kT} \cdot \frac{\Delta z}{2u_a}\right) + \rho_0$$

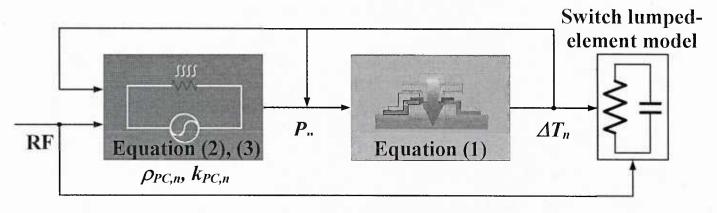
k, q, τ_0 , E_P , V, Δz and u_a indicate Boltzmann constant, elementary charge, time constant for trapped electron, Fermi level, applied voltage, short trap distance, and effective thickness of PC layer, respectively



Y. Shim and M. Rais-Zadeh, IEEE EDL, 2014

Power Handling Analysis Nonlinear Joule-Heating Model

 Power handling capability (IIP₃, P_{1dB}) is analyzed using non-linear electro-thermal model of GeTe switches.



Electro-thermal model of GeTe switch

$$H(\omega) = \frac{\Delta T}{P} = \frac{1}{V_E} \cdot \frac{t_E[(t_{PC}/k_{PC}) \cdot ((\tanh \beta_{PC})/\beta_{PC}) + R_B]}{1 + j\omega C_E t_E[(t_{PC}/k_{PC}) \cdot ((\tanh \beta_{PC})/\beta_{PC}) + R_B]}$$

$$\rho_{PC} = \frac{kT \cdot \tau_0}{(q\Delta z)^2 \cdot N_T} \cdot e^{(E_C - E_F)/kT} \cdot \cosh^{-1} \left(\frac{qV}{kT} \cdot \frac{\Delta z}{2u_a}\right) + \rho_0$$

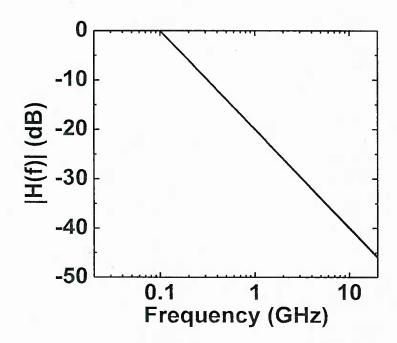
$$k_{PC} = a \cdot \exp[-(T - T_0)/b] + c$$

3: Thermal resistivity modeling

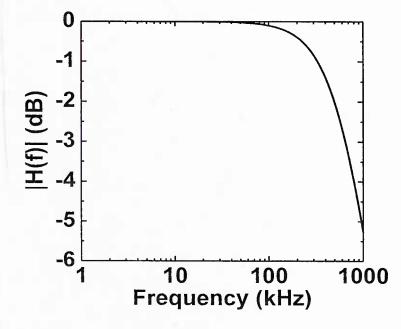


Power Handling Analysis Heat Transfer Function

- Frequency response of heat transfer function shows low pass filtering behavior.
- For the simulated structure the thermal 3dB BW is ~600 kHz.



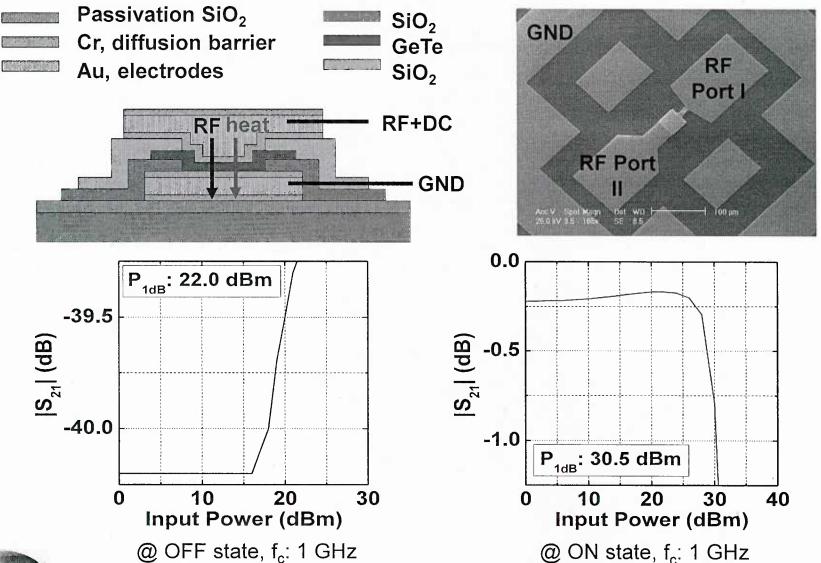
Heat transfer function Frequency response up to 20 GHz



Heat transfer function Frequency response up to 1 MHz

Y. Shim and M. Rais-Zadeh, IEEE EDL, 2014

GeTe Switch with Direct Heating - Type A Simulated P_{1dB} with modeling parameters

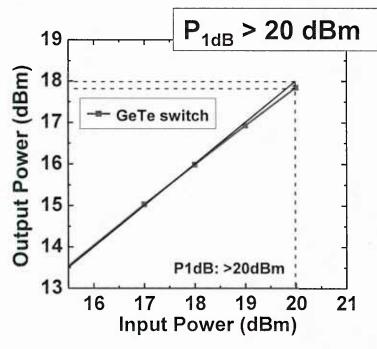




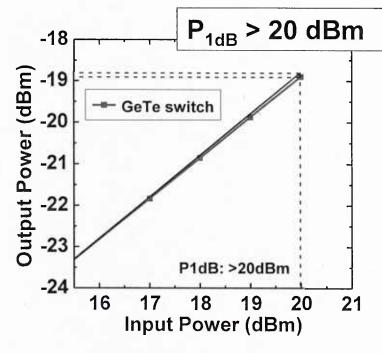
Y. Shim and M. Rais-Zadeh, IEEE EDL, 2014

GeTe Switch with Direct Heating - Type A Measured P_{1dB}

- P_{1dB} is also measured at both crystalline and amorphous states.
- Due to the tool limitation, P_{1dB} is only verified to be better than 20 dBm.



Measured P_{1dB} at 1 GHz (Crystalline state)



Measured P_{1dB} at 1 GHz (Amorphous state)



GeTe Switch with Direct Heating - Type A Simulated IIP₃ with modeling parameters

- IIP₃ is simulated with modeling parameters.
- Smaller offset frequency provides worse IIP₃ due to low-pass filtering effect in the heat transfer function.

#	State	F _C (GHz)	ΔF (KHz)	δ	IIP ₃ :MODEL (dBm)
1	OFF	0.5	50	1.0	27.1
2	OFF	0.5	1000	1.0	27.2
3	OFF	2.0	50	1.0	33.2
4	OFF	0.5	50	0.2	34.1
5	ON	0.5	50	1.0	36.7
6	ON	0.5	1000	1.0	39.1
7	ON	2.0	50	1.0	36.7
8	ON	0.5	50	0.2	50.7



Y. Shim and M. Rais-Zadeh, IEEE EDL, 2014

GeTe Switch with Direct Heating - Type A Simulated IIP₃ with modeling parameters

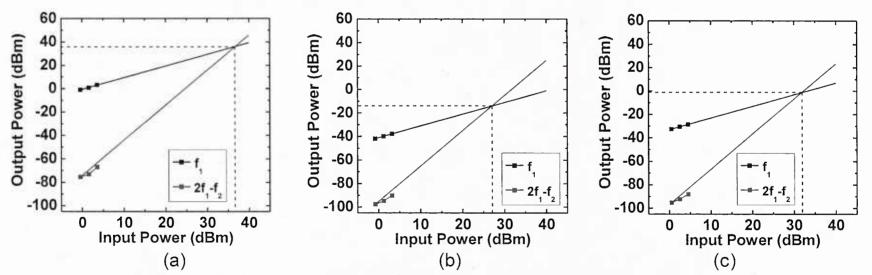
- IIP₃ is simulated with modeling parameters.
- Center frequency does not have any effect on IIP₃ at the ON state.
- Higher center frequency result in better IIP₃ at the OFF state.

#	State	F _C (GHz)	∆F (KHz)	δ	IIP ₃ :MODEL (dBm)
1	OFF	0.5	50	1.0	27.1
2	OFF	0.5	1000	1.0	27.2
3	OFF	2.0	50	1.0	33.2
4	OFF	0.5	50	0.2	34.1
5	ON	0.5	50	1.0	36.7
6	ON	0.5	1000	1.0	39.1
7	ON	2.0	50	1.0	36.7
8	ON	0.5	50	0.2	50.7



GeTe Switch with Direct Heating - Type A Measured IIP₃ with

- IIP₃ of fabricated devices is measured at both states.
- Better IIP₃ is observed at ON state (expected).
- Better IIP₃ in the amorphous state is observed at higher frequencies (feed-through capacitance dominated region).
- IIP₃ does not show much frequency dependency at crystalline state. ₹



Measured IIP₃ at the ON state with f₁: 2 GHz, Δ f: 50 kHz (IIP₃: 35.9 dBm). Measured IIP₃ at the OFF state (b) f₁: 500 MHz, Δ f: 50 kHz (IIP₃: 27.0 dBm); (c) f₁: 2 GHz, Δ f: 50 kHz (IIP₃: 31.9 dBm).

Y. Shim and M. Rais-Zadeh, IEEE EDL,

GeTe Switch with Direct Heating - Type A Simulation / Measurement Result

- IIP₃ of fabricated devices is measured at both states.
- Better IIP₃ is observed at ON state (predicted).
- Measurements and simulations are in very good agreement.

#	State	F _C (GHz)	∆F (KHZ)	δ	IIP ₃ :MODEL (dBm)	IIP ₃ :MEASURED (dBm)
1	OFF	0.5	50	1.0	27.1	27.0
2	OFF	0.5	1000	1.0	27.2	
3	OFF	2.0	50	1.0	33.2	31.9
4	OFF	0.5	50	0.2	34.1	
5	ON	0.5	50	1.0	36.7	35.9
6	ON	0.5	1000	1.0	39.1	
7	ON	2.0	50	1.0	36.7	35.9
8	ON	0.5	50	0.2	50.7	



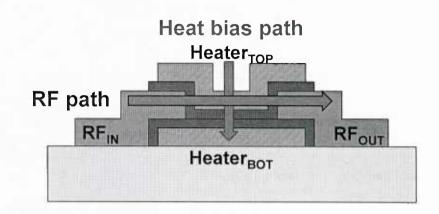
Outline

- Motivation & Introduction
- GeTe Vias as RF Ohmic Switches
 - Intrinsic RF Properties
 - Phase-Transition Characteristics
 - Power Handling Capability
- New GeTe Switch Design
 - Design Consideration
 - RF & Heat Simulation
 - Measurement Results
- Future Plans



GeTe Switch with Separate Electrodes - Type B New Design Consideration

- The previous design is built for basic characterization of GeTe.
- For more reliable phasetransition and better isolation, heater and RF electrodes are separated.



- In this new design, heater bias and RF signal paths are separated while still maintaining a direct heating scheme.
 - More convenient, lower power, and easier transition with direct heating.
 - Heater bias path can be optimized for more reliable transitions.
 - RF path can be optimized for lower loss and better isolation.

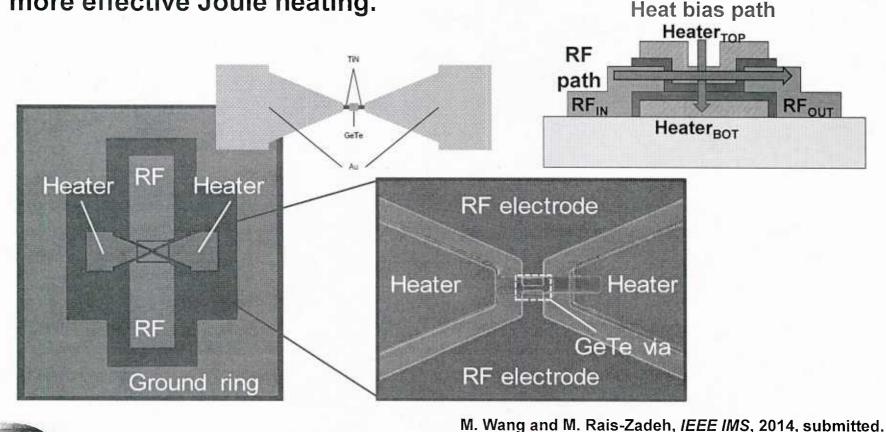


GeTe Switch with Separate Electrodes - Type B Device Principle of Operation

Two GeTe layers are included to provide separation of RF electrodes and heater electrodes.

Heater electrodes are composed of high-resistivity material for

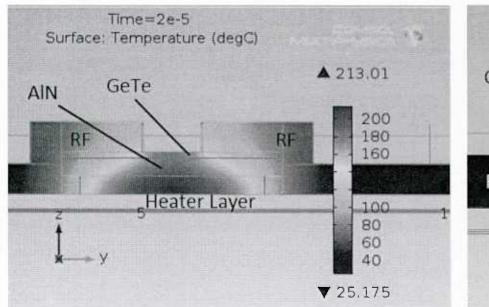
more effective Joule heating.

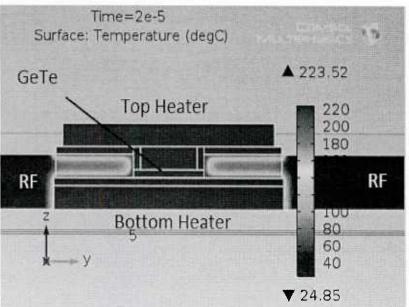




GeTe Switch with Separate Electrodes - Type B Heat Simulation

- The most important advantage of direct heating scheme is that lower power is required to phase transition the via.
- It also does not have the problem of local cold spot at low power levels.
- Simulations are performed using COMSOL.





Cross-section view of temperature distribution when a 20 µs current pulse of (left) 50 mA is applied to an indirectly heated via, and (right) 5.5 mA is applied to the presented directly heated via

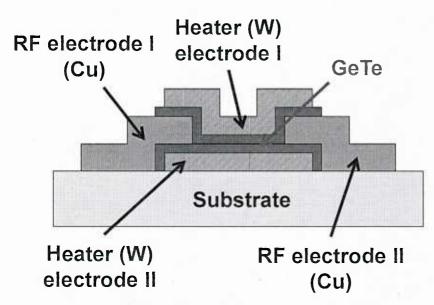


GeTe Switch with Separate Electrodes - Type B RF Simulation

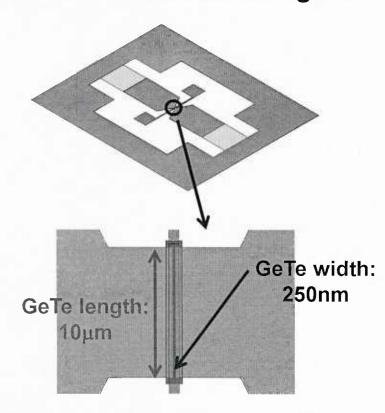
 For verification of the RF performance, 3D electromagnetic simulation using HFSS is performed.

Each simulation is performed with different widths and lengths for

the switch via.



Schematic diagram of GeTe switch with direct heating structure

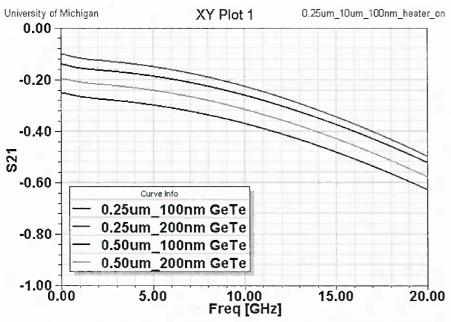


3D model and top-down view of GeTe switch with direct heater for HFSS simulation

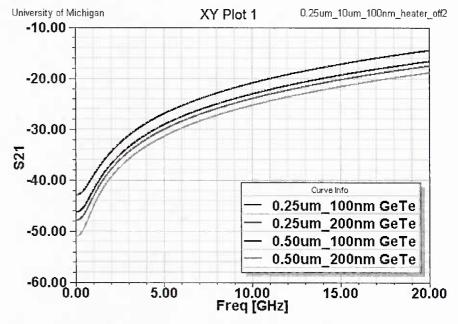


GeTe Switch with Separate Electrodes - Type B RF Simulation Results

• As the width of GeTe via increases (0.25 to 0.50 μ m), isolation is improved while insertion loss is exacerbated. Thicker GeTe layer can compensate this with reduced resistance; smaller parasitic capacitance between RF electrode and heater layer can further improve the isolation.



Simulated S₂₁ at the crystalline state with different length and thickness of GeTe via.



Simulated S_{21} at the amorpheous state with different length and thickness of GeTe via.



GeTe Switch with Separate Electrodes - Type B Fabrication Process

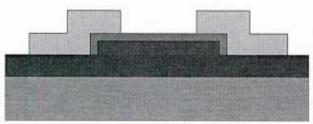
1. Bot. heater layer deposition (TiN or other HR metals) on a Si passivated with AIN



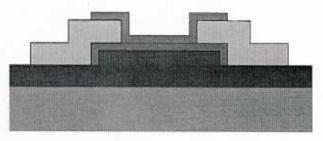
2. 1st GeTe layer deposition



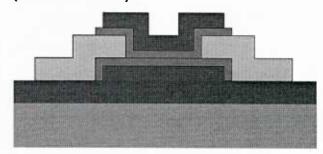
3. RF electrode deposition (Ti/Au/Ti)



4. 2nd GeTe layer deposition



5. Top heater layer deposition (TiN or TaN)

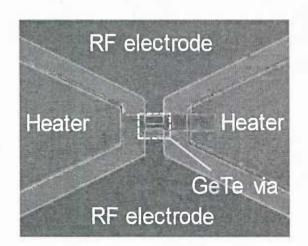


M. Wang and M. Rais-Zadeh, *IEEE IMS*, 2014, nominated for best student paper award

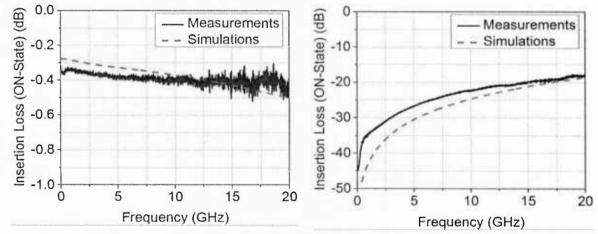


GeTe Switch with Separate Electrodes - Type B Measurement Result: R_{on} & R_{off}

- Preliminary devices are fabricated on a Silicon substrate with AIN Passivation layer.
- Results show promising performance w/ cutoff frequency> 4.1 THz (note that these are measured on Silicon).
- This is the first 4-terminal directly heated phase change switch. IL can be improved by reducing the spacing between RF electrodes.



SEM image of a 4-terminal directly heated GeTe switch



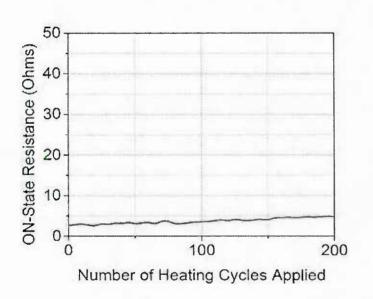
Measured Response of the switch, left: ON state IL; Right: OFF state isolation.

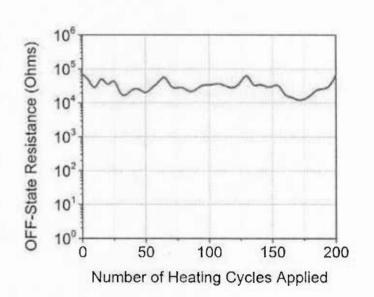
M. Wang and M. Rais-Zadeh, IEEE IMS, 2014



GeTe Switch with Separate Electrodes - Type B Life Cycle

- Switches are manually cycles (need to automate this).
- The power consumption of the switch is smaller than indirectly heated switches by more than an order of magnitude¹.





DC resistance values versus the number of heating cycles applied at (left) the crystalline state and (right) the amorphous state.

using an independent Electron Device chalcogenide phase-change RF El-Hinnawy, et al.,

GeTe Switch with Separate Electrodes - Type B Simulation Result: IIP₃

 Higher power RF signal can contribute unintended crystallization or amorphization effect in Type B switch when its effective ONresistance is the same as Type A switch.

#	State	F _C (GHz)	∆F (KHZ)	IIP ₃ :MODEL (dBm) TYPE A	IIP ₃ :MODEL (dBm) Type B
1	OFF	0.5	50	27.1	32.1
2	OFF	0.5	1000	27.2	32.6
3	OFF	2.0	50	33.2	38.1
5	ON	0.5	50	36.7	40.5
6	ON	0.5	1000	39.1	41.0
7	ON	2.0	50	36.7	40.5

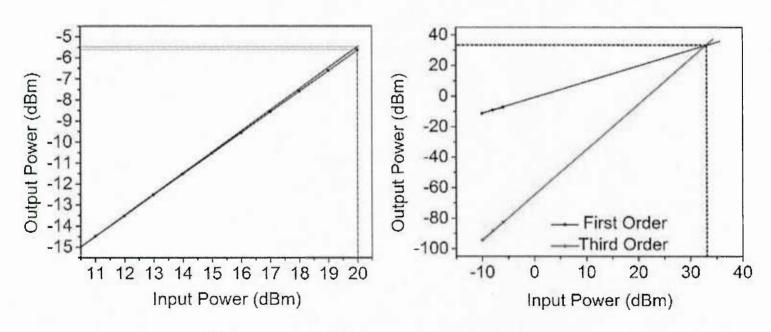
Simulated IIP₃ for different f_c and Δf



M. Wang, Y. Shim, and M. Rais-Zadeh, IEEE EDL, 2014

GeTe Switch with Separate Electrodes - Type B Measurement Result: IIP₃

- Measured IIP₃ > 33 dBm.
- P₁dB cannot be measured but higher than 20 dBm.
- · Results in good agreement with the electro-thermal model.

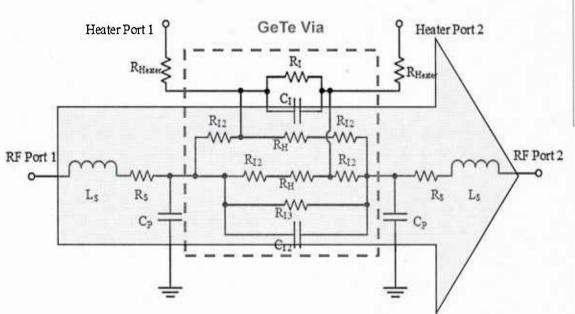


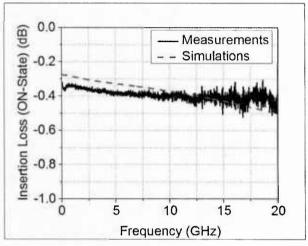
Measured P₁dB (@2GHz, OFF-state) and IIP₃ (@2GHz, 50 kHz offset, ON state)



M. Wang, Y. Shim, and M. Rais-Zadeh, IEEE IMS, 2014

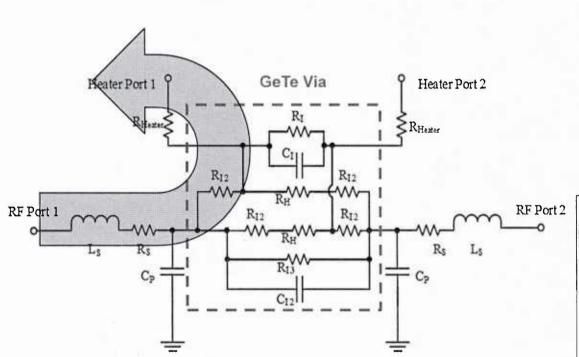
GeTe Switch with Separate Electrodes - Type B Electrical Model

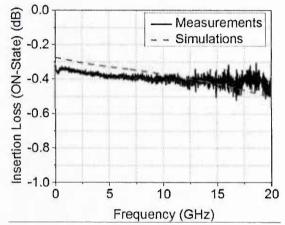


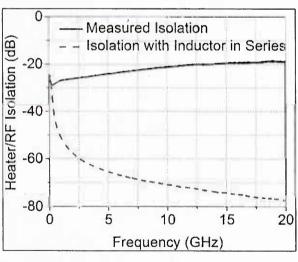


M. Wang, Y. Shim, and M. Rais-Zadeh, IEEE IMS, 2014

GeTe Switch with Separate Electrodes - Type B Electrical Model







GeTe Switch with Separate Electrodes - Type B Summary of Results

	[1]	[2]	[3]
ON-state DC resistance	1.2 Ω	5 Ω	3.9 Ω
OFF/ON resistance ratio	9.2×10 ⁴	0.96×10 ⁴	~0.5×10 ⁴
Insertion loss at 20 GHz	< 0.3 dB	< 0.6 dB	< 0.5 dB
Isolation at 20 GHz	12 dB	20 dB	> 18 dB
Via Capacitance (C _{OFF})	18.1 fF	8.5 fF	9.9 fF
Cut-off Frequency	7.3 THz	3.7 THz	> 4.1 THz
Switching time per 1 cycle		600.5 µs	404 µs
Power consumption per cycle	4.5 W	92 mW	82 mW
P _{1dB}	> 35 dBm	>20 dBm	> 20 dBm
IIP ₃	_	33 dBm	> 30 dBm

¹ N. El-Hinnawy, et al., IEEE EDL, vol. 34, no. 10, pp. 1313-1315, Oct. 2013.

² M. Wang, Y. Shim, and M. Rais-Zadeh, IEEE EDL, 2014

³ M. Wang and M. Rais-Zadeh, IEEE IMS, 2014



GeTe Switch with Separate Electrodes - Type B Summary of Results

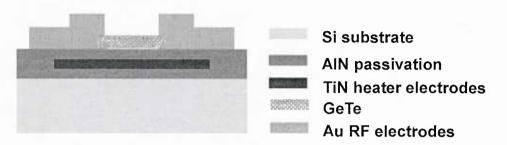
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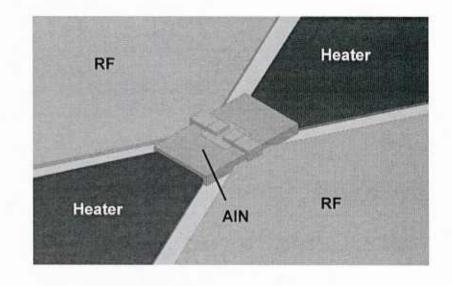
N. El-Hinnawy, et al., IEEE EDL, vol. 34, no. 10, pp. 1313-1315, Oct. 2013.
 M. Wang, Y. Shim, and M. Rais-Zadeh, IEEE EDL, 2014
 M. Wang and M. Rais-Zadeh, IEEE IMS, 2014



GeTe Switch with Separate Electrodes - Type C Indirect Heating Scheme

- Electrical isolation between heater and RF path
- Heater layer underneath
 GeTe with AIN isolation
- RF electrodes laterally connected
- GeTe heated through thermal conduction
- Parasitic elements are significantly reduced
- Promising for highfrequency operation
- Fabrication and measurements ongoing



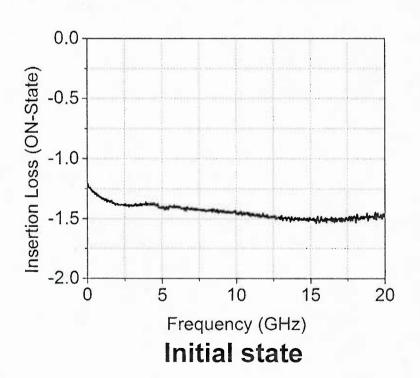


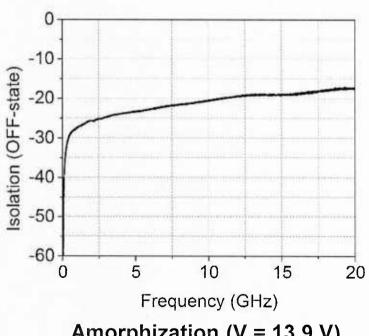


GeTe Switch with Separate Electrodes - Type C **Preliminary Results**

S-parameters Measurements

- Initial ON-state insertion loss: 1 to 2 dB
- Off-state isolation: ~18 dB at 20 GHz
- Initial DC ON resistance: ~10 Ω
- Typical initial OFF resistance: $\sim 70 \text{ k}\Omega$



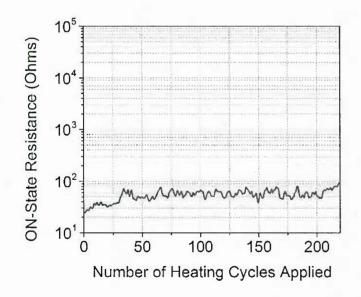


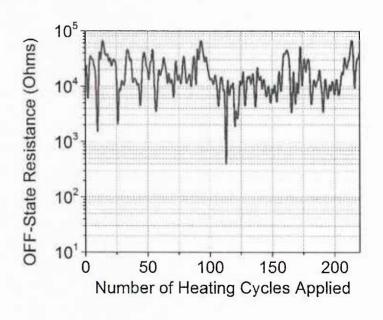




GeTe Switch with Separate Electrodes - Type C Repeatability

- Repeated heating pulses applied (220 cycles)
- ON-state resistances
 - $\sim 10 \Omega 50 \Omega$
 - Can be improved by changing size
- OFF-state resistances
 - Typically 5 kΩ 70 kΩ







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 - Intrinsic RF Properties
 - Phase-Transition Characteristics
 - Power Handling Capability
- New GeTe Switch Design
 - Design Consideration
 - RF & Heat Simulation
 - Initial Measurement Result
- Future Plans



Program Schedule

- Single task; 1 year seedling project.
- Proposal: support 1 student.
- Project started officially in Jan 2013; received funding in two increments (last one received in Jan. 2014).

Subtask	D	Phase I									
. #	Description of activities			Q2		Q3			Q4		
ST1	Design and simulation of optimized device architecture to achieve the proposed performance specs and metrics										n
ST2	Development and optimization of fabrication process including choice of heater material/contact metal/ and stack thickness										
And the factor of the factor o	Fabrication of micro devices using resistance change materials							No.	11/1/2 Move to		
S S S S S S S S S S S S S S S S S S S	Test and characterization of DC performance of switches including ON-resistance and ON/OFF resistance Ratio										Mp Mp Mp
interest of the second	Test and characterization of RF performance of switches including insertion loss, parasitic capacitance, and power handling capability										THE STREET
Deliver- ables	Submit quarterly report to DARPA										
De al	Deliver 5 functional samples										



Future Plans

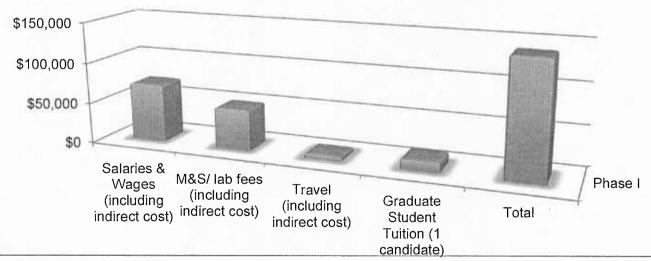
- GeTe switch directly heated: optimize fabrication process & stack materials/ characterize power handling capability / test repeated cycling (currently manually cycled).
- GeTe switch indirectly heated: change via size to reduce via resistance; Characterize optimal heating condition to best crystallize GeTe; Use two GeTe layers; Use top passivation to protect GeTe and get better heating conditions; Characterize best RF electrode material to minimize damage to GeTe (e.g., diffusion)
- Preparation of heating current biasing system.
- Preparation of long life cycling test setup.
- Funding: will discuss separately.
 - One student graduated. The undergrad student working on this project continued now as a PhD student. Also a post-doc is recently hired.



Funding Status-Proposed

- Single task; 1 year seedling project.
- Proposal: support 1 student.
- Project started officially in Jan 2013; received funding in two increments (last one received in Jan. 2014).

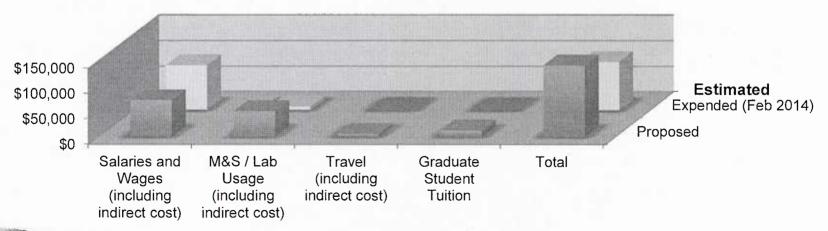
Categories and Timeline	Total (1/10/13-8/31/14)				
Salaries & Wages (including indirect cost)	\$71,628				
M&S/ lab fees (including indirect cost)	\$50,664				
Travel (including indirect cost)	\$5,443				
Graduate Student Tuition (1 candidate)	\$12,428				
Total	\$140,163				





Funding Status- Update

- One student graduated (joined Broadcom). The undergrad student working on this project continued now as a PhD student. Also a post-doc is recently hired.
- Project started officially in Jan 2013. Funding spent as proposed. Now in no cost extension till 5/31/2014.
- Proposal submitted to ACT (w/ SRC) rejected.
- Requesting funding for 2 years to work on various aspects of RF phase change switch/ switch network.





change

Funding Status- Proposed Budget

Categories and Timeline	Year 2	Year 3	Total 6/1/14 - 5/31/16		
Categories and Timeline	6/1/14 - 5/31/15	6/1/15 - 5/31/16			
Direct Salaries and Wages					
Prof. M. Rais-Zadeh, Project Director					
5% Academic Year	\$5,202	\$5,358	\$10,559		
25% 2 Summer Months	\$5,611	\$5,779	\$11,391		
Post-Doctoral Research Fellow					
50%, Full Year	\$25,563	\$26,329	\$51,892		
Graduate Student Research Assistants					
1 @ 50% Full Year	\$28,528	\$29,384	\$57,911		
Subtotal Salaries and Wages	\$64,903	\$66,850	\$131,753		
Staff Benefits @ 20% GSRA, 30% others	\$16,618	\$17,117	\$33,735		
SUBTOTAL SALARIES AND BENEFITS	\$81,521	\$83,967	\$165,488		
Materials and Supplies			· · · · · · · · · · · · · · · · · · ·		
LNF User Fees, 1 user	\$20,000	\$20,000	\$40,000		
Masks (10 Plates)	\$3,800	\$3,800	\$7,600		
Glass wafers, Si Wafers, Sapphire wafers	\$3,031	\$3,031	\$6,063		
Various Processing Supplies, Chemicals, etc.	\$5,000	\$5,000	\$10,000		
Misc. Supplies, telephone charges, mailing, etc.	\$2,000	\$2,000	\$4,000		
SUBTOTAL MATERIALS/SUPPLIES	\$33,831	\$33,831	\$67,663		
Travel	\$3,500	\$3,500	\$7,000		
Graduate Student Tuition (1 non-candidate)	\$21,853	\$22,945	\$44,798		
SUBTOTAL EQUIPMENT	\$0	\$0	\$0		
Subtotal Direct Costs	\$140,705	\$144,243	\$284,948		
Subtotal Indirect Costs (55.5%)	\$65,963	\$67,320	\$133,283		
Total	\$206,668	\$211,563	\$418,231		

